

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Todd <i>et al.</i>
Appl. No.	:	10/623,482
Filed	:	July 18, 2003
For	:	METHOD TO FORM ULTRA HIGH QUALITY SILICON- CONTAINING COMPOUND LAYERS
Examiner	:	Ron Everett Pompey
Group Art Unit	:	2812

Supplemental Response**Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

This is a supplemental response to the final Office Action sent electronically on November 27, 2006. Applicants request full consideration of the remarks contained herein.

A Listing of the Claims begins on page 2 of this paper.

Summary of Interview begins on page 4 of this paper.

Remarks/Arguments begin on page 5 of this paper.